

ABSTRACT OF THE DISCLOSURE

A fabrication method of an IPS mode LCD including forming a pixel electrode and a common electrode on a first substrate; forming a passivation layer on the pixel electrode and common electrode; forming a black matrix layer on a second substrate; forming a color filter layer on the black matrix layer; forming an overcoat layer on the color filter layer; and irradiating an ion beam on the passivation film on the first substrate and the overcoat layer on the second substrate to perform an orientation treatment of the passivation film and the overcoat layer. The common electrode, the pixel electrode, the gate line and the data line are formed in a stripe configuration or a zigzag configuration. In a zigzag configuration, there is at least one bent portion in the configuration.